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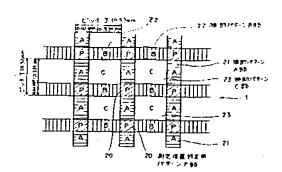
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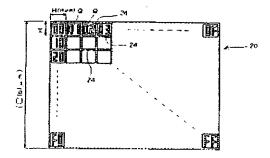
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TITLE

STANDARD SAMPLE AND POSITION

CORRECTING METHOD





ABSTRACT :

PURPOSE: To easily detect a predetermined position in a standard sample by forming position specifying patterns at an interval and forming three or more kinds of auxiliary pattern parts having mutually different patterns so as to surround said position specifying patterns.

CONSTITUTION: The patterns of an aligning standard sample 1 are divided into a grid form and auxiliary pattern A-part 21, B-part 22 are C-part 23 are respectively formed at a specified pitch in the up-and-down, left-and-right and oblique directions of a measuring position specifying main pattern P-part 20. Grids 24 divided at a pitch H are formed to the P-part 20 and entirely different patterns Q, Q... showing lines and rows in two digits using hexadecimal digits 0-F are provided in the grids as discrimination patterns. Respectively different uniform patterns A-C are formed to the A-part 21 - the C-part 23 and which direction the P-part 20 is present is cleared when the patterns A-C are observed. That is, for example, in such a case that the A-part 21 is observed when the sample 1 is measured by a scanning type tunnel microscope, the sample 1 is relatively moved in an upper or lower direction to reach the P-part 20.

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